PATENT

Atty Docket No.: 10005급원신EIVED

CENTRAL FAX CENTER

In The U.S. Patent and Trademark Office

DEC 2 7 2005

In Re the Application of:

Inventor(s):

Osamu Samuel NAKAGAWA

MANNAVA & KANG, P.C.

Confirmation No.:

3642

Serial No.:

09/891,325

Examiner: Chuong A. Luu

Filed:

June 27, 2001

Group Art Unit:

2818

Temothy Kang Resudo 46, 423

Title:

HIGH-DIELECTRIC CONSTANT METAL-INSULATOR METAL CAPACITOR IN VLSI MULTI-LEVEL METALLIZATION SYSTEMS

MAIL STOP AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

CERTIFICATE OF FACSIMILE TO THE USPTO

I hereby certify that this correspondence is being transmitted to the Patent and Trademark Office facsimile number (571) 273-8300 on December 27, 2005. This correspondence contains the following document(s):

I sheet of Transmittal Letter for Response/Amendment (2 copies).

9 sheets of Request for Reconsideration.

Respectfully submitted,

MANNAVA & KANG, P.C.

December 27, 2005

Ashok K. Mannava

Reg. No.: 45,301

MANNAVA & KANG, P.C. 8221 Old Courthouse Road

Suite 104

Vienna, VA 22182 (703) 652-3822

(703) 880-5270 (facsimile)

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MANNAVA & KANG, CENTRAL FAX CENTER (FAX) 703 880 5270 DEC-27-2005(TUE) 16:12

P. 002/012

Intellectual Property Administration P. O. Box 272400 Fort Collins, Colorado 80527-2400

DEC 2 7 2005

PATENT APPLICATION

ATTORNEY DOCKET NO. ___10005208-1

IN THE

UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor(s):

Osamu Samuel NAKAGAWA

Confirmation No.: 3642

Application No.: 09/891,325

Examiner: Chuong A. Luu

Filing Date:

June 27, 2001

Group Art Unit: 2818

Title:

HIGH-DIELECTRIC CONSTANT METAL-INSULATOR METAL CAPACITOR IN VLSI

MULTI-LEVEL METALLIZATION SYSTEMS

Mall Stop Amendment **Commissioner For Patents** PO Box 1450 Alexandria, VA 22313-1450

TRANSMITTAL LETTER FOR RESPONSE/AMENDMENT

Sir:					·-	_	
frar	ismitted h	erewith is/are the fo	llowing in	the above-identified	application:		
X)		e/Amendment		()	• •		me to respond
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<u> </u>	Other: _				<u> </u>	(fee \$_	<u> </u>
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to Deposit Account 08-2025. At any time during the pendency of this application, please charge any fees required or credit any overpayment to Deposit Account 08-2025 pursuant to 37 CFR 1.25. Additionally please charge any fees to Deposit Account 08-2025 under 37 CFR 1.16, 1.17, 1.19, 1.20 and 1.21. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

(X) I hereby certify that this paper is being transmitted to the Patent and Trademark Office facsimile number <u>(571) 273-8300</u> on <u>Dec. 27, 2005</u> Number of pages: 12

Typed Name: Judy H. Chi

Signature

Osamu Samuel NAKAGAWA

Ashok K. Mannava

Attorney/Agent for Applicant(s)

Reg. No. 45,301

(FAX)703 880 5270

P. 003/012

PATENT APPLICATION

Intellectual Property Administration P. O. Box 272400 Fort Collins, Colorado 80527-2400

IN THE

UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor(s):

Osamu Samuel NAKAGAWA

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Examiner: Chuong A. Luu

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RECEIVED CENTRAL FAX CENTER

Mail Stop Amendment **Commissioner For Patents** PO Box 1450 Alexandria, VA 22313-1450 DEC 2 7 2005

TRANSMITTAL LETTER FOR RESPONSE/AMENDMENT

e:	_
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Transmitted herewith is/are the following in the above-identified application: .

Response/Amendment

() Petition to extend time to respond

New fee as calculated below ()

() Supplemental Declaration

No additional fee (X)

Other: _

	(tee	5	_)
ΠÝ			7

·(1) ·FOR	(2) CLAIMS REMAINING AFTER AMENDMENT	(3) (4) (5) NUMBER HIGHEST NUMBER PRESENT EXTRA PREVIOUSLY PAID FOR EXTRA				ı	(6) RATE	ADDI	(7) ITIONAL EES	
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number <u>(571) 273-8300</u> on <u>Doc 27 2005</u> Number of pages: 12

Typed Name: Judy H, Ch

Signature:

Osamu Samuel NAKAGAWA

Ashok K. Mannava

Attorney/Agent for Applicant(s)

Reg. No. 45,301

Date: Dec. 27, 2005

RECEIVED **CENTRAL FAX CENTER**

HEWLETT-PACKARD COMPANY Intellectual Property Administration

P.O. Box 272408 Fort Collins, Colorado 80527-2400 DEC 2 7 2005

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CAPACITOR IN VLSI MULTI-LEVEL METALLIZATION SYSTEMS

MAIL STOP AMENDMENT

Commissioner for Patents P.O. Box 1450

Alexandria, VA 22313-1450

REQUEST FOR RECONSIDERATION

Sir:

In response to the Office Action dated September 27, 2005, kindly consider the remarks as follows.